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# Ammonia oxidation on Ir(1 1 1): Why Ir is more selective to N<sub>2</sub> than Pt

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#### ABSTRACT

 $NH_3$  does not dissociate on a clean  $Ir(1\,1\,1)$  surface, but dissociation can be induced by radiation, which yields all possible  $NH_{xad}$  species.  $NH_{ad}$  is the most stable and it is the only intermediate found at room temperature.  $NH_{ad}$  decomposes between 350 and 500 K, yielding  $NH_3$  (g) and  $N_{ad}$ , which desorbs as  $N_2$  between 550 and 700 K. Adsorbed oxygen atoms induce  $NH_3$  dissociation between 300 and 400 K, forming  $NH_{ad}$  and  $NH_2$ 0.  $NH_{ad}$  decomposes further between 350 and 450 K, forming  $NH_{ad}$  and  $NH_2$ 0.  $NH_{ad}$  decomposes further between 350 and 450 K, forming  $NH_{ad}$  and  $NH_2$ 0.  $NH_{ad}$  decomposition during ammonia oxidation showed a mismatch between the change of the surface coverage (from  $NH_{ad}$  to  $NH_{ad}$ ) and that in the gas phase (from  $NH_2$  to  $NH_2$ ). This is explained by a higher barrier for  $NH_2$ 0 (g) formation as compared to  $NH_2$ 2 formation on  $NH_2$ 11. On  $NH_2$ 111) the difference in barrier height for  $NH_2$ 12. NO formation is smaller, which explains why  $NH_2$ 13 more selective to  $NH_2$ 13 more selective to  $NH_2$ 13 more selective to  $NH_2$ 3 more selective to  $NH_2$ 4 more selective to  $NH_2$ 4 more selective to  $NH_2$ 5 more sel

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#### 1. Introduction

Ammonia is formed as an unwanted side product in several industrial processes. The removal of ammonia can be achieved in a selective catalytic reaction between NH<sub>3</sub> and O<sub>2</sub>. The desired products in this case are N<sub>2</sub> and H<sub>2</sub>O. A catalyst for this process needs to be both active and selective towards N<sub>2</sub> rather than NO<sub>x</sub>. Ir based catalysts show the desired activity and selectivity [1]. Catalytic oxidation of NH<sub>3</sub> on Ir has been studied before by several authors, both for high surface area catalysts and single crystal surfaces [1-8]. In previous publications we reported on NH<sub>3</sub> decomposition and oxidation on Ir(110) [4-8] and a model was proposed to explain the selectivity towards N<sub>2</sub> instead of NO [8] for this particular Ir surface. The (110) surface shows 'special' behavior in the sense that N<sub>2</sub> formation on this surface is accelerated by the presence of O<sub>ad</sub> due to repulsive interactions between  $O_{ad}$  and  $N_{ad}$  [7,9]. The (111) surface, which is usually the most common plane on small catalyst particles, is a more representative candidate to be used as a model to study the behavior of Ir catalysts. We already published some desorption spectra and temperature programmed reaction data that were obtained on the Ir(111) surface [8]. The present paper describes new results that were obtained on Ir(111) using high resolution, fast XPS, which gives information about the nature and concentration of adsorbates  $\mathit{during}$  a catalytic reaction. A similar study was reported for Pt(111) by Mieher and Ho [10], who used thermal desorption and EELS to study  $O_{ad}$ -induced NH $_3$  decomposition. Although there are many more surface science studies concerning NH $_3$  oxidation, on various surfaces (Cu [11], Ru [12], Ag [13], Ni [14] and Rh [15]), we limit the discussion here to Ir and compare it to Pt (used as a catalyst in the Ostwald process [16] to make NO $_{x}$  from NH $_3$ ), two metals that show different selectivity in the NH $_3$  oxidation reaction.

## 2. Experimental

The vacuum systems used for the TPD and XPS measurements (performed at the SuperESCA beamline of ELETTRA, the synchrotron radiation facility in Trieste, Italy) are described in detail elsewhere [7]. The pressures reported here are uncorrected ion gauge readings. The Ir single crystal (diam. 1 cm, thickness 2 mm) was cut and polished to within 0.1° of the desired (1 1 1) orientation. It was cleaned using Ar<sup>+</sup> sputtering and annealing (1400 K) cycles, followed by oxygen treatments. The oxygen was removed either by flashing to 1400 K or by heating in the presence of hydrogen. In the latter case, H<sub>2</sub> was removed by a final flash to 700 K. The cleanliness of the sample was checked by XPS, showing no oxygen and carbon contamination. The N1s spectra were measured with a photon energy of 480 eV, for the O1s spectra a photon energy of 650 eV was

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used. Temperature programmed XPS (TP-XPS) measurements were performed using heating rates between 0.3 and 0.65 K s<sup>-1</sup>. The different core level regions were measured in a separate experiment, i.e. during one experiment either O1s or N1s could be measured. The XP spectra were evaluated, after subtraction of a linear background, by fitting the peaks with a Doniach–Šunjić lineshape convoluted with a Gaussian function [17] to account for experimental and thermal broadening. The binding energy (BE) values are reported here with respect to the Fermi level, measured using the same excitation energy that was used to measure the spectra.

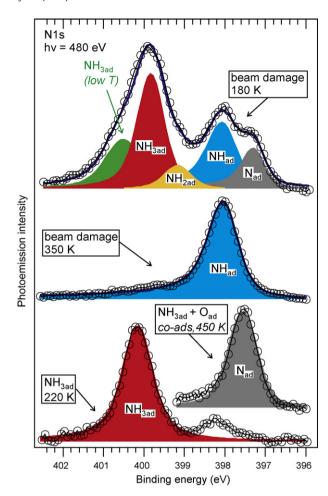
Quantification of the O1s signal intensity was done using an oxygen-saturated surface as a reference, prepared by dosing  $O_2$  at 300 K. Earlier studies report a saturation coverage of 0.5 ML, based on the  $(2 \times 2)$  LEED pattern observed after dosing  $O_2$  at room temperature [18–21]. Recently, the adsorption of oxygen was studied using XPS, and a saturation coverage of 0.38 ML was reported [22]. This value was used to calibrate the oxygen coverage in our experiments. Quantification of the N1s spectra was more complicated and was done indirectly. In an experiment where  $O_{ad}$  reacted with NH3ad to form  $O_{ad}$  (discussed in detail in 3.2) the decrease of the  $O_{ad}$  signal was used to calculate the  $O_{ad}$  coverage based on the stoichiometry of the reaction.

In our earlier XPS studies beam-induced  $NH_{3ad}$  dissociation was observed [6]. In experiments where we wanted to keep the beam damage as low as possible, the steps preceding the actual measurements were preformed in the absence of radiation and the heating rate was doubled, so that the experiment would be faster and thus, the beam damage would be minimized. The sample position was also regularly changed to check that the areas which had not been exposed to the beam showed the same changes. In this way, we ensured that the data reported here do not suffer from beam damage.

In the study presented here, beam damage was used as a tool to create NH<sub>xad</sub> species on the surface and to study their thermal behavior. The beam flux on the sample is typically  $10^{11}$  to  $10^{13}$  photons  $s^{-1}$ , depending on the settings of the exit slit and the photon energy. The spot size is determined by the size of the exit slit of the monochromator, which was chosen such that the beam spot on the sample is between  $\sim$ 1 and 2 mm in our experiment. The beam damage in the XPS experiment is thought to be primarily due to the photoelectrons generated by the X-rays, rather than a direct X-ray induced process. This is confirmed by the fact that NH<sub>3ad</sub> dissociation was also found after irradiation with 60 eV electrons. The latter method was used to obtain temperature programmed desorption (TPD) results and has been used before by other authors who studied surfaces on which NH<sub>3ad</sub>, like on Ir(111) [8,23], does not dissociate [13,24-26]. Since we use beam damage here merely as a tool, to study the thermal behavior of NH<sub>xad</sub> species, the beam damage process will not be discussed in more detail here.

### 3. Results and discussion

Fig. 1 shows schematically how the different N1s components found throughout the experiments were assigned to the different NH<sub>xad</sub> species, by careful comparison with thermal desorption experiments. The binding energy of NH<sub>3ad</sub> was determined by adsorption of NH<sub>3</sub> at 100 K followed by heating to 220 K. The binding energy of N<sub>ad</sub> was established by heating a co-adsorbed O<sub>ad</sub>/NH<sub>3ad</sub> layer. Above 400 K one N1s species exists, which desorbs as N<sub>2</sub> (discussed in detail in Section 3.2). It should be noted here that the BE value of N<sub>ad</sub> is sensitive to the chemical environment of the N<sub>ad</sub>, and shifts of  $\sim\!0.3\,\text{eV}$  were seen during the experiments. During heating of a beam-damaged NH<sub>xad</sub> layer, a single species exists on the surface between 300 and 400 K, which decomposes into N<sub>ad</sub> between 400 and 500 K. On Ir(110) a species with a very



**Fig. 1.** N1s spectra taken during different experiments, illustrating how the peak shape and binding energy for the different  $NH_{xad}$  species was determined. See text for details. The experimental points are represented by open circles, while the fitting result is indicated by a solid line.

similar binding energy and similar thermal behavior was identified as NH<sub>ad</sub>. Thus, the same assignment was used here [6]. The spectral shapes and binding energies of the afore mentioned species were used to analyze the composition of the mixture of NH<sub>xad</sub> species existing on the surface at 180 K after beam-induced decomposition has occurred. The NH<sub>3ad</sub> BE value is affected by the chemical environment of the NH3ad, especially in the low temperature regime, where the presence of another  $NH_{3ad}$  species (top spectrum) causes a downward shift of  $\sim$ 0.3 eV as compared to the spectrum where only one  $NH_{3ad}$  species is present. Next to the already identified species, two other components had to be used to properly fit the spectrum. One component with a BE of 399.2 eV was assigned to NH<sub>2ad</sub>, based on its BE value which is just between that of NH<sub>3ad</sub> and NH<sub>ad</sub>. Another component at the high binding energy side was assigned to another adsorbed NH<sub>3</sub> species present only at low temperatures. In the present article, we limit the discussion on the NH<sub>3</sub> surface chemistry to the temperature regime above 200 K, where only one form of chemisorbed NH3 is present. A more detailed discussion on low temperature adsorption states of NH3 on various substrates can be found in Ref. [6] and references therein. For the O1s region only one species, assigned to O<sub>ad</sub>, was applied to fit the O1s spectra for all experimental conditions. Other possible O-containing species, such as NO and H<sub>2</sub>O, would appear at significantly different binding energies and would be easily distinguished (see Table 1).

The binding energy values that were found on  $Ir(1 \ 1 \ 1)$  are summarized in Table 1, together with values found earlier on  $Ir(1 \ 1 \ 0)$ .

**Table 1** Binding energies (eV) for nitrogen and oxygen species found during ammonia oxidation on  $Ir(1\,1\,1)$  and  $Ir(1\,1\,0)$  [6,7]. Note that the O1s BE values reported in Ref. [7] were off by  $\sim\!0.5\,\text{eV}$ . In this table the correct values for these O1s species on  $Ir(1\,1\,0)$  are reported, with respect to the Fermi edge.

Species	N1s, Ir(111)	N1s, Ir(110)	O1s, Ir(1 1 1)	O1s, Ir(110)
NH <sub>3ad</sub>	399.8-400.1	400.2	-	-
$NH_{2ad}$	399.2	-	-	-
NH <sub>ad</sub>	398.1	398.3	-	-
N <sub>ad</sub>	397.3-397.6	397.2	_	-
O <sub>ad</sub>	-	_	530.0	529.9
NO <sub>ad</sub>	Not obs.	400.5	Not obs.	532.5
$H_2O$	-	_	Not obs.	532.2

For the BE values reported in Refs. [6,7] an incorrect value for the Fermi edge was used, resulting in a consequent deviation of  $0.7 \, \text{eV} \, (\text{N1s})$  and  $0.5 \, \text{eV} \, (\text{O1s})$  from the correct values. This data has been revisited using a proper Fermi edge correction and the correct BE values for  $Ir(1\,1\,0)$  are shown in Table 1. The values found for  $Ir(1\,1\,0)$  and  $Ir(1\,1\,1)$  are in excellent agreement. The differences in BE that exist between this study and those reported for NO on  $Ir(1\,1\,0)$  by de Wolf et al. [9,27] are most probably due to the fact that in those studies Ir photoemission peaks were used for BE calibration, instead of the Fermi edge as used in the present study.

## 3.1. $NH_{xad}$ surface chemistry

Fig. 2 shows the results of two experiments in which an adsorbed NH<sub>3</sub> layer (saturation, 5 L) was heated. The process was followed by TPD and by TP-XPS. In the first experiment (shown left), radiation damage was kept to the minimum. In the second experiment (shown right), beam damage was intentionally created before the heating was started.<sup>1</sup> In the absence of beam damage, NH<sub>3</sub> desorbs molecularly in a broad temperature region between 100 and 400 K [8]. Panel (a) only shows the temperature region that matches the TP-XPS data. The inset shows the full desorption trace, including the physisorbed states present below 150 K (discussed in detail elsewhere, see for example Ref. [6]). In the corresponding TP-XPS experiment, NH<sub>ad</sub> slowly builds up due to beam damage. This shows that beam damage, although present, is a slow process, and it can easily be distinguished from the real chemistry.

At 200 K the irradiated NH3ad layer (Fig. 2, righthand side) contains all possible NH<sub>xad</sub> species, in different concentrations. NH<sub>2ad</sub> decomposes around 230 K (into NH<sub>ad</sub>) and NH<sub>3ad</sub> desorbs molecularly between 200 and 350 K. The atomic nitrogen that was initially present disappears around 300 K, but not due to desorption of N<sub>2</sub>. The decrease of the N<sub>ad</sub> is assigned to hydrogenation of N<sub>ad</sub> into  $NH_{ad}$ . On  $Ir(1\,1\,0)$  it was shown before that  $N_{ad}$  can be hydrogenated below 300 K [6]. This shows that  $NH_{ad}$  is the most stable  $NH_{xad}$ species and that conversion of NH<sub>2ad</sub> and N<sub>ad</sub> (in the presence of H<sub>ad</sub>) to NH<sub>ad</sub> readily occurs around or below room temperature. The NH<sub>ad</sub> concentration increases between 200 and 400 K, reaching a maximum of  $\sim$ 0.23 ML. It is interesting to note here that a  $(2 \times 2)$  LEED pattern could be generated [shown in the inset of Fig. 2(d)] when the Ir(111) sample was exposed to NH<sub>3</sub> at 300 K and irradiated with 60 eV electrons. We tentatively assign this to a  $p(2 \times 2)$  overlayer of  $NH_{ad}$  on the sample, with a coverage of  ${\sim}0.25$  ML, in line with the NH<sub>ad</sub> coverage found by XPS at  ${\sim}300$  K. On Pt(111)NH<sub>ad</sub> was also found to be the most stable NH<sub>xad</sub> species in experiments where an NH<sub>3ad</sub> layer was irradiated and heated [24]. Hydrogenation of N<sub>ad</sub> to NH<sub>ad</sub> on Pt(111) also occurs between 200 and 300 K [25].

NH<sub>ad</sub> decomposes between 360 and 530 K, forming 0.1 ML of N<sub>ad</sub> and releasing 0.13 ML 'N' into the vacuum. The TPD experiment [Fig. 2(b)], gives some information on the desorbing products around this temperature. The most obvious candidate is N2, and this is indeed observed at these temperatures in the gas phase during TPD. A detailed analysis of the TPD result reveals that desorption of N<sub>2</sub> is not the only pathway. First of all, the NH<sub>3</sub> desorption peak between 380 and 500 K is not observed when there is no beam damage. This suggests that it is due to NH<sub>3</sub> formation at this temperature by hydrogenation of NH<sub>ad</sub>. In such a reaction three NH<sub>ad</sub> species are needed to generate one NH3 molecule, and two Nad species are formed (Eq. (1)). The H<sub>2</sub> desorption trace presents further evidence for such a reaction: the desorption peaks below 350 K are due to combination of H<sub>ad</sub>[28], formed during (radiation-induced) NH<sub>3ad</sub> decomposition, while the desorption peak between 440 and 590 K is due to decomposition of NH<sub>ad</sub>. The latter peak is much smaller than what would be expected when decomposition of NH<sub>ad</sub> into N<sub>ad</sub> and H<sub>2</sub> is the only mechanism (peak ratio 2:1). We suggest the following mechanisms during NH<sub>ad</sub> decomposition: at the onset of NH<sub>ad</sub> decomposition (Eq. (2)) some N<sub>ad</sub> and H<sub>ad</sub> are created, while the NH<sub>ad</sub> concentration is still high. Free H<sub>ad</sub> on the surface combines to H<sub>2</sub>(g) below 350 K [28], so that any hydrogen formed > 400 K will have a short residence time. It is, however, just enough for hydrogenation of NH<sub>ad</sub>, forming ultimately NH<sub>3</sub>, which desorbs upon formation (Eq. (3)). At higher temperatures, the NH<sub>ad</sub> concentration has decreased and molecular hydrogen desorption is favored over NH<sub>ad</sub> hydrogenation. The N<sub>ad</sub> formed after NH<sub>ad</sub> decomposition desorbs as N2 between 400 and 700 K.

$$3 NH_{ad} \rightarrow 2 N_{ad} + NH_3(g) \tag{1}$$

$$NH_{ad} \rightarrow N_{ad} + H_{ad}$$
 (2)

$$NH_{ad} + 2H_{ad} \rightarrow NH_3(g) \tag{3}$$

# 3.2. Influence of $O_{ad}$ on $NH_{3ad}$ decomposition

The influence of Oad on the NHxad chemistry was studied in an experiment in which an O<sub>ad</sub> covered surface (0.38 ML) was exposed to NH<sub>3</sub> (5 L, 150 K) and heated afterwards. The results are shown in Fig. 3. In the TPD experiment, the H<sub>2</sub>O desorption trace displays four different peak maxima between 150 and 400 K. On the basis of our XPS results the different peaks can be attributed to different surface reactions. The H<sub>2</sub>O desorption around 190 K corresponds to the desorption temperature of adsorbed H<sub>2</sub>O (see supplementary information, Fig. S1). It is therefore tentatively assigned to water that was adsorbed from the background gas or a small H<sub>2</sub>O contamination in the NH<sub>3</sub> used for the TPD experiments. In the XPS experiment, however, the O1s spectra did not reveal any adsorbed water. It could also correspond to a low temperature reaction between O<sub>ad</sub> and NH<sub>3</sub>. Evidence for such a reaction can be found in the presence of  $\mathrm{NH}_{\mathrm{2ad}}$  already at the onset of the XPS measurement. The peak at 220 K is accompanied by decomposition of NH<sub>2ad</sub> into NH<sub>ad</sub>. All these low temperature processes cause only a minor decrease of the Oad concentration and might be influenced by beam damage. The most obvious influence of O<sub>ad</sub> is seen above 280 K, where the TP-XPS data shows reaction of NH3ad to NH<sub>ad</sub>, which starts at 280 K. It is accompanied by a significant O<sub>ad</sub> consumption and a  $H_2O$  desorption peak. At 350 K the  $NH_{ad}$  concentration reaches a maximum of 0.05 ML, after which it decreases. This decrease is accompanied by a fast increase of the N<sub>ad</sub> concentration, O<sub>ad</sub> consumption, a H<sub>2</sub>O desorption peak (400 K) and the

 $<sup>^1</sup>$  For the TPD experiment the adsorbed NH $_3$  layer was exposed to 60 eV electrons, for  $\sim \! 5$  min. In the TP-XPS experiment the exposure to 480 eV X-rays (used to measure the N1s level) was 25 min. before the measurement was started. Our TP-XPS results show that TPD and XPS can be safely compared: The only possible products that beam-induced dissociation can yield are NH $_{2ad}$ , NH $_{ad}$  and N $_{ad}$ , irrespective of the type of radiation used. During TP-XPS both NH $_{2ad}$  and N $_{ad}$  were found to be converted into NH $_{ad}$ . It is therefore very likely that a similar process would yield an NH $_{ad}$ -covered surface at 300 K after electron-beam-induced damage.

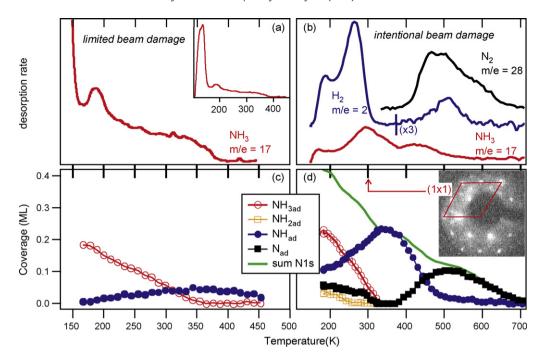
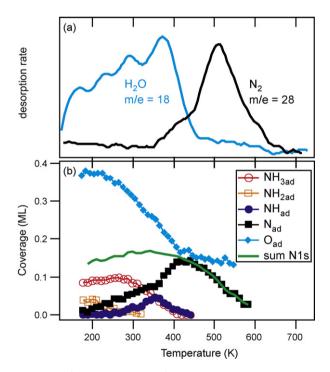


Fig. 2. (a) TPD  $(0.4\,\mathrm{K\,s^{-1}})\,\mathrm{NH_3}$  desorbs molecularly, between 100 and 400 K. The main panel shows a zoom-in of the temperature region that matches the XPS data. The inset shows the desorption spectrum of the surface after saturation with NH<sub>3</sub>. (c) TP-XPS,  $(0.65\,\mathrm{K\,s^{-1}})\,\mathrm{of}$  an adsorbed NH<sub>3</sub> layer. The slow build-up of NH<sub>ad</sub> is due to radiation-induced dissociation. (b) TPD  $(3\,\mathrm{K\,s^{-1}})\,\mathrm{of}$  an irradiated NH<sub>3ad</sub> layer, showing desorption of N<sub>2</sub> and H<sub>2</sub>, decomposition products of NH<sub>3</sub>. Note that the H<sub>2</sub> trace > 400 K is multiplied by 3. (d) TP-XPS  $(0.5\,\mathrm{K\,s^{-1}})\,\mathrm{after}$  beam-induced dissociation of an NH<sub>3ad</sub> layer, showing the formation of various NH<sub>xad</sub> species and their thermal behavior during heating. The inset of panel (d) shows a  $(2\times2)$  LEED pattern, observed after irradiation  $(60\,\mathrm{eV})\,\mathrm{electrons}$ , during NH<sub>3</sub> dosing at 300 K. It is tentatively assigned to a  $p(2\times2)$ -NH<sub>ad</sub> layer with a coverage of  $\sim$ 0.25 ML.



**Fig. 3.** TPD (1 K s $^{-1}$ ) and TP-XPS (0.65 K s $^{-1}$ ) after saturation (0.38 ML O $_{ad}$ ) with O $_2$  at 300 K and 5 L NH $_3$  (150 K). Panel (a) shows that H $_2$ O desorbs in four different peaks, between 150 and 400 K. N $_2$  desorbs between 450 and 650 K. Hydrogen adsorption was not found at all. Panel (b) shows the corresponding TP-XPS results, showing the O-assisted decomposition of NH $_{3ad}$  to NH $_{ad}$  between 300 and 450 K and O-assisted NH $_{ad}$  decomposition into N $_{ad}$  between 350 and 450 K.

onset of  $N_2(g)$  formation, i.e., at this temperature  $NH_{ad}$  reacts with  $O_{ad}$  to  $N_{ad}$ ,  $H_2O(g)$  and some  $N_2(g)$ . We cannot completely exclude that  $N_{ad}$  formed between 200 and 350 K is due to beam-induced dissociation. We therefore do not interpret this in detail and limit

the discussion here to  $N_{ad}$  formation above 350 K that is more obviously due to surface chemistry, as corroborated by the TPD where beam damage was absent.  $NH_{ad}$  decomposition in the presence of  $O_{ad}$  occurs at a significantly lower temperature than  $NH_{ad}$  decomposition in the absence of  $O_{ad}$ , i.e.  $NH_{ad}$  dehydrogenation is assisted by atomic oxygen, similar to what was found on  $Ir(1\,1\,0)$  [7]. At 420 K all  $NH_{xad}$  is converted into  $N_{ad}$ , and the  $O_{ad}$  concentration stabilizes at  $\sim\!0.15$  ML. The further slow decrease of the  $O_{ad}$  signal is assigned to reactions with background gases such as  $H_2$  and CO. The  $N_2$  desorption temperature is not affected very much by the presence of  $O_{ad}$ , in contrast to the strong downward shift found on  $Ir(1\,1\,0)$  [4,7,27,29].

The role of oxygen in  $NH_3$  dissociation can be described in two ways, either via a direct reaction between  $O_{ad}$  and  $NH_{3ad}$ , or by an indirect influence of the oxygen. The adsorption of oxygen influences the reactivity of the metal surface and can thereby indirectly enhance  $NH_3$  decomposition [30]. The latter model was used to explain oxygen-enhanced dissociation of  $NH_{3ad}$  on Ir(100) [3]. In their experiments water formation was not found, the only products being  $H_2$  and  $N_2$ , which excludes the direct reaction between adsorbates. In our experiments water formation is found while hydrogen desorption is absent. We can therefore not distinguish between the two models.

The formation of  $NO_{ad}$ , NO(g) or  $N_2O(g)$  was not observed on  $Ir(1\,1\,1)$ , not even during an experiment in which a mixed  $NH_{3ad}/O_{ad}$  layer was heated in the presence of  $O_2$  (g) (see supporting information, Fig. S2). This is in contrast to our findings on  $Ir(1\,1\,0)$ , where  $NO_{ad}$  formation was found when  $O_{ad}$  and  $N_{ad}$  were both present above  $400\,K$ . On  $Ir(1\,1\,1)$  all the 'ingredients' to form  $NO_{ad}$  are present on the surface, i.e.  $NH_{ad}$  and  $O_{ad}$  co-exist on the surface between 300 and  $400\,K$  and  $N_{ad}$  and  $O_{ad}$  co-exist on the surface between 200 and  $500\,K$ . This is due to the fact that the dissociated state is more stable than  $NO_{ad}$  on  $Ir(1\,1\,1)$ , i.e. there is no thermodynamic driving force towards NO formation (see also the discussion in Section 3.4).

#### 3.3. Temperature programmed ammonia oxidation

The gas phase products found during temperature programmed  $NH_3$  oxidation on  $Ir(1\,1\,1)$  have been reported briefly in Ref. [8], for three different reactant ratios. In the present study we report new results obtained using a combination of TP-XPS to determine the nature and concentration of the surface species and measurements of the gas phase composition during temperature programmed ammonia oxidation. Fig. 4 shows the results for  $NH_3/O_2$  ratios of 1:1 and 1:4. A more comprehensive TPR study for different reactant ratios and absolute pressures can be found in supporting information, Fig. S3. From the data presented there, it becomes clear that the absolute pressure only affects the reaction rate, not the temperature where the gas phase selectivity changes from  $N_2$  to NO. This fact allows us to safely compare the TPR and TP-XPS data shown in Fig. 4, even though the reactant pressures differ by one order of magnitude.

### 3.3.1. Ratio 1:1

The XPS measurements were done in the following way: first the surface was exposed to NH<sub>3</sub> (5  $\times$  10<sup>-8</sup> mbar) and subsequently the oxygen pressure was established. The dissociative adsorption of O<sub>2</sub> is partially inhibited by the presence of NH<sub>3ad</sub> resulting in an  $O_{ad}$  coverage of only 0.16 ML (40% of saturation coverage) at the beginning of the heating. The behavior of the surface species in this experiment is similar to what was observed for a mixed NH3ad/Oad overlayer, i.e., formation of NH<sub>ad</sub> around 300 K and formation of  $N_{ad}$  around 400 K (Fig. 3). From XPS it can be seen that  $N_{ad}$  accumulates on the surface, while the equilibrium O<sub>ad</sub> concentration is almost zero. However, O<sub>2</sub> adsorption/decomposition still occurs, as evidenced by the gas phase, showing continuous N<sub>2</sub> formation for  $T > 400 \,\mathrm{K}$ . Above 500 K the surface composition changes and  $N_{\mathrm{ad}}$ is gradually replaced by  $O_{ad}$ . Up to 650 K, the  $O_{ad}$  concentration rapidly increases up to 0.11 ML (at 650 K), while further heating only results in a very slow increase. Formation of NO<sub>ad</sub> was not observed in this experiment. It is important to note that the change of gas phase selectivity to N<sub>2</sub> occurs 80 K higher than the change of surface composition. This means that N<sub>2</sub> is the only gas phase product at 600 K, even though the surface concentrations of N<sub>ad</sub> and O<sub>ad</sub> at this temperature are equally large.

# 3.3.2. Ratio 1:4

A change of the gas phase reactant ratio from 1:1 to 1:4 does not affect the low temperature NH<sub>3</sub> + O<sub>ad</sub> surface chemistry. At 400 K, at the onset of the reaction, the surface is covered with N<sub>ad</sub> (0.27 ML) and the O<sub>ad</sub> concentration is very low. In a separate experiment where the reaction (ratio 1:4) was stopped around 400 K, the reactants were pumped away, and the surface was cooled to 250 K, a  $(2 \times 2)$  LEED pattern was visible [shown in the inset of panel (b)]. It is assigned to a  $p(2 \times 2)$ - $N_{ad}$  structure with a coverage of  ${\sim}0.25\,\text{ML},$  in line with the  $N_{ad}$  coverage determined by XPS. The most important influence of the higher O<sub>2</sub> partial pressure on the surface composition is observed around 500 K, where the change of surface composition from N<sub>ad</sub> to O<sub>ad</sub> occurs faster and at a lower temperature than for the 1:1 ratio. A maximum O<sub>ad</sub> concentration of 0.23 ML is reached, about twice the amount found for the 1:1 ratio. For the higher O<sub>2</sub> partial pressure, both the surface composition and the gas phase selectivity change at lower temperatures, but the T-difference between surface composition change and gas phase selectivity change is  $\sim$ 80 K, for both reactant ratios.

#### 3.4. Comparison between Pt and Ir: understanding selectivity

Platinum and iridium show significantly different catalytic properties when used as a catalyst for ammonia oxidation [1]. In this section we discuss the differences and propose an explanation

for this based on the adsorption energies of the adsorbates on the surface.

Ammonia dissociates on more open Ir surfaces, such as Ir(110) and Ir(510) [6,5], but not on the smooth, close-packed (111) surface [23]. A slightly sputtered (111) surface is also active for NH<sub>3</sub> dissociation [8], showing that the dissociation activity is related to the presence of low-coordinated Ir atoms (defects). On Pt, on the other hand, defects do not help to dissociate NH<sub>3</sub> at low temperature [26,31,32], although NH<sub>3</sub> dissociation was observed in the presence of NH<sub>3</sub> (g) above 400 K [33,34].

For both metals O<sub>ad</sub> has a beneficial effect on NH<sub>3ad</sub> decomposition: on Pt it is essential for low temperature dissociation [10,31,35], on Ir it is essential to dissociate NH3ad on the closepacked (111) surface, and it lowers the NH<sub>ad</sub> decomposition temperature on several Ir surfaces [7]. On Ir(110) it also lowers the temperature for  $N_{ad}$  combination to  $N_2$  (g) [6]. The most pronounced difference between Pt and Ir is found during temperature programmed ammonia oxidation. On Pt surfaces, formation of NO<sub>ad</sub> occurs readily, even at 250 K [26,35,36], and NO is the dominant product of the ammonia oxidation reaction on Pt catalysts. On Ir on the other hand, NO formation is more difficult. This difference is most clearly seen when the surface composition and gas phase products are measured during temperature programmed reaction, as is done in this study and also in, for example, Refs. [8,26]. On Pt, the surface composition is directly reflected in the gas phase product distribution: a surface predominantly covered with Nad produces mainly N2, an Oad-covered surface produces NO [26]. On Ir the surface composition and gas phase selectivity change are not synchronized, and temperature differences of 80 K [Ir(111)] up to 200 K [Ir(1 1 0)] have been found.

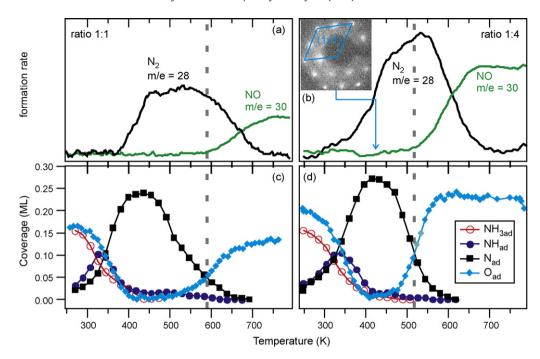
The formation rate of  $N_2$  and NO as a function of surface coverage and temperature can in first approximation be described with the kinetic expressions shown in equations 4 and 5, in which  $k_{N_2}$  and  $k_{NO}$  represent the rate constants for  $N_2$  and NO formation, and  $\theta_N$  and  $\theta_O$  represent the coverage of  $N_{ad}$  and  $O_{ad}$ :

$$\frac{\mathrm{d}[N_2]}{\mathrm{d}t} = k_{N_2} \theta_N^2 \tag{4}$$

$$\frac{\mathrm{d}[NO]}{\mathrm{d}t} = k_{NO}\theta_N\theta_O \tag{5}$$

The experimental observations show that the NO formation rate on Ir(111) does not depend directly on  $\theta_N$  and  $\theta_O$ . This means that the selectivity is determined by a difference between  $k_{N_2}$  and  $k_{NO}$ , i.e. the activation energy of N<sub>2</sub> formation should be significantly lower than that of NO formation. We have constructed an energy scheme (Fig. 5) for N<sub>2</sub> and NO formation on Ir(111) and Pt(111) by using theoretically predicted values from literature [37,38]. Both studies were performed by the same group, and a very similar approach was used for both surfaces. We used the adsorption energies obtained with the PW91 functional to produce the figure. The activation energies were calculated from the adsorption energies of the atomic reactants using the Brønsted–Evans–Polanyi relationship [39,40] from the work of Nørskov et al. [41].

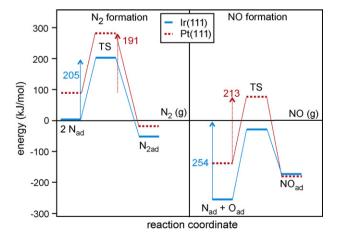
From this figure the difference between Pt and Ir becomes clear. The barriers for  $N_2$  formation on both surfaces are around  $\sim 200 \, \text{kJ} \, \text{mol}^{-1}$ . More importantly, the transition state energy lies above the energy of the  $N_2$  molecule in the gas phase. This means that the  $N_2$  molecule will immediately desorb upon formation and the experimentally observed barrier is equal to the barrier height for  $N_2$  formation. For NO formation the situation is different. The activation barrier to form the NO molecule is  $\sim 20 \, \text{kJ} \, \text{mol}^{-1}$  higher than to form  $N_2$  and it is similar both on Pt and Ir. For Pt the energy of the transition state is above that of NO(g), i.e., NO will desorb upon formation, and the experimentally observed activation energy is equal to the barrier height. On Ir, on the other hand, the energy of the transition state is *below* that of NO(g), meaning that additional



**Fig. 4.** Temperature programmed reaction (TPR,  $0.7\,\mathrm{K\,s^{-1}}$ ) and TP-XPS ( $0.4\,\mathrm{K\,s^{-1}}$ ) during ammonia oxidation, for two reactant ratios. The NH<sub>3</sub> pressure was kept constant at  $5\times10^{-8}$  mbar during the TP-XPS, while for the TPR data a constant NH<sub>3</sub> pressure of  $5\times10^{-7}$  mbar was used. The O<sub>2</sub> pressure was adjusted according to the desired ratio. For both ratios, the surface coverage changes from N<sub>ad</sub> to O<sub>ad</sub>, but the selectivity change in the gas phase from N<sub>2</sub> to NO is shifted by 80 K to higher temperatures.

energy  $(30 \text{ kJ} \text{ mol}^{-1})$  is needed to desorb the NO molecule in the gas phase. The result is that the barrier for NO(g) formation on Pt is only  $\sim 20 \text{ kJ} \text{ mol}^{-1}$  higher than that of N<sub>2</sub> formation, whereas on Ir(1 1 1) it is  $\sim 50 \text{ kJ} \text{ mol}^{-1}$  higher. The reason behind this difference is the much stronger adsorption of the atomic species on Ir as compared to Pt. This explains the stronger preference for N<sub>2</sub> formation on Ir(1 1 1).

The shift of the NO formation to lower temperatures with increasing  $O_2$  partial pressure can be explained by coverage effect which are not present in the ideal theoretical model. We offer here two different explanations, which could both play a role: (i) the  $O_{ad}$  concentration reaches higher values for higher  $O_2$  partial pressures. As a result the  $O_{ad}$  adsorption energy decreases, which means that energy of the reactants and the transition state shifts upward, bringing the transition state closer to that of NO(g), thus lowering the barrier for NO(g) formation. (ii) An alternative explanation can



**Fig. 5.** Schematic energy diagram for  $N_2$  and NO formation on Pt(111) and Ir(111). The values for Ir(111) were adapted from Ref. [37]. The values for Pt(111) were adapted from Ref. [38]. The experimentally relevant barriers included in the figure.

be directly derived from the energy scheme in Fig. 5. The formation of NO $_{\rm ad}$  becomes feasible at higher temperature, but it is endothermic, so the equilibrium is shifted toward the side of the atomic adsorbates. A high concentration of O $_{\rm ad}$  can inhibit NO dissociation, and the NO $_{\rm ad}$  that is formed desorbs rather than dissociates.

### 4. Summary and conclusions

The NH $_3$  surface chemistry on Ir(111) has been studied using XPS and desorption measurements. NH $_3$  does not dissociate on Ir(111), but radiation can induce dissociation. On a beam-damaged sample at low temperature a mixture of NH $_{3ad}$ , NH $_{2ad}$ , NH $_{ad}$  and N $_{ad}$  is found, but N $_{ad}$  and NH $_{2ad}$  converted below 300 K to NH $_{ad}$ , which was found to be the most stable NH $_{xad}$  surface species. It decomposes between 400 and 500 K, during which N $_{ad}$ , N $_2$ , NH $_3$  (g) and some H $_2$  are formed, in a complex interplay between NH $_{ad}$  decomposition, NH $_{ad}$  hydrogenation, and H $_2$  desorption.

The presence of  $O_{ad}$  enables  $NH_3$  dissociation at low temperature, forming  $NH_{ad}$  between 280 and 400 K. Atomic oxygen also destabilizes  $NH_{ad}$ , which reacts with  $O_{ad}$  to  $N_{ad}$  above 350 K (instead of 400 K found in the absence of  $O_{ad}$ ). The formation of  $NO_{ad}$  or  $NO\left(g\right)$  was not observed, in contrast to findings on  $Ir(1\,1\,0)$ , where  $NO_{ad}$  was formed above 400 K.

During temperature programmed ammonia oxidation the surface composition below 500 K is dominated by  $N_{ad}$ , above 500 K the surface composition changes and  $O_{ad}$  is the only adsorbate present in measurable quantities above 650 K. The temperature at which the surface composition changes depends on the exact  $NH_3/O_2$  reactant ratio. The gas phase selectivity also shifts, from  $N_2$  to NO, but this occurs  $\sim\!\!80\,\mathrm{K}$  higher than the change of surface composition. This finding is explained by looking at the barriers for  $N_2$  vs. NO formation on Ir(111). The strong adsorption of atomic adsorbates on Ir(111) gives rise to a barrier that is 50 kJ mol $^{-1}$  higher than that of  $N_2$  formation on the same surface. On Pt(111) the adsorption of atomic adsorbates is weaker, and the barriers for NO and  $N_2$  formation differ by only 20 kJ mol $^{-1}$ .

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### Appendix A. Supplementary data

Supplementary data associated with this article can be found, in the online version, at doi:10.1016/j.cattod.2010.03.049.

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